Design Flow Enhancements for DNA Arrays*

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Abstract

DNA probe arrays have recently emerged as one of the core genomic technologies. Exploiting analogies between manufacturing processes for DNA arrays and for VLSI chips, we demonstrate the potential for transfer of methodologies from the 40-year old field of electronic design automation to the newer DNA array design field. Our main contributions in this paper are the following. (1) We give a new design flow for DNA arrays which enhances current methodologies by adding flow-awareness to each optimization step and introducing feedback loops. (2) We propose solution methods for new formulations integrating multiple design steps, including probe selection, placement, and embedding. (3) We give results of a comprehensive experimental study showing that significant improvements in solution quality can be achieved by using the enhanced methodologies.

1 Introduction

DNA probe arrays – DNA arrays or DNA chips for short – have recently emerged as one of the core genome technologies. They provide a cost-effective method for obtaining fast and accurate results in a wide range of genomic analyses, including gene expression monitoring, mutation detection, and single nucleotide polymorphism analysis (see [27] for a survey). The number of applications is growing at an exponential rate [16, 35], already covering a diversity of fields ranging from health care to environmental sciences and law enforcement. The reasons for this rapid acceptance of DNA arrays are a unique combination of robust manufacturing, massive parallel measurement capabilities, and highly accurate and reproducible results.

Today, most DNA arrays are manufactured through a highly scalable process, referred to as *Very Large-Scale Immobilized Polymer Synthesis (VLSIPS)*, that combines photolithographic technologies adapted from the semiconductor industry with combinatorial chemistry [1, 2, 13]. Similar to Very Large Scale Integration (VLSI) circuit manufacturing, multiple copies of a DNA array are simultaneously synthesized on a *wafer*, typically made out of quartz. To initiate synthesis, linker molecules including a photo-labile protective group are attached to the wafer, forming a regular 2-dimensional pattern of synthesis sites. Probe synthesis then proceeds in successive steps, with one nucleotide (A, C, T, or G) being synthesized at a selected set of sites in each step. To select which sites will receive nucleotides, photolithographic *masks* are placed over the wafer. Exposure to light de-protects linker molecules at the non-masked sites. Once the desired sites have been activated in this way, a solution containing a single type of nucleotide (which bears its own photo-labile protection group to prevent the probe from growing by more than one nucleotide) is flushed over the wafer's surface. Protected nucleotides attach to the unprotected linkers, initiating the probe synthesis process. In each subsequent step, a new mask is used to enable selective de-protection and single-nucleotide synthesis. This cycle is repeated until all probes have been fully synthesized.

As the number of DNA array designs is expected to ramp up in coming years with the ever-growing number of applications [16, 35], there is an urgent need for high-quality software tools to assist in the design and manufacturing process. The biggest challenges to rapid growth of DNA array technology are the drastic increase in design sizes with simultaneous decrease of array cell sizes – next-generation designs are envisioned to have hundreds of millions of cells of sub-micron size [2, 27] – and the increased complexity of the design process, which leads to unpredictability of design quality and design turnaround time. Surprisingly enough, despite huge research efforts invested in DNA array applications, very few works are devoted to computer-aided optimization of DNA array design and manufacturing. Current design practices are dominated by ad-hoc heuristics incorporated in proprietary tools with unknown suboptimality. This will soon become a bottleneck for the next generation of high-density arrays, such as the ones currently being de-

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signed at Perlegen [2].

In this paper we exploit the similarities between manufacturing processes for DNA arrays and VLSI chips and demonstrate significant potential for transfer of electronic design automation methodologies [11, 30] to the newer DNA array design field. Our main contributions in this paper are the following:

- We give a new design flow for DNA arrays, which enhances current methodologies by adding *flow-awareness* to each optimization step and introducing *feedback loops* (Section 2).
- We propose new formulations and solution methods that integrate probe placement and embedding with probe selection and deposition sequence design (Section 3).
- We empirically demonstrate significant solution quality improvements for the enhanced methodologies. In particular, we show that 5-7% improvement in border length can be achieved over the highest-quality scalable flow previously reported in the literature [23] by a tighter integration of probe placement and embedding (more precisely, by replacing synchronous initial probe embedding with the so-called "as soon as possible" embedding, see Section 4). Furthermore, we show that up to 15% improvement in border length can be achieved by integrating probe selection with probe placement and embedding (Section 5).

2 Main Steps of the DNA Array Design Flow

In this section we introduce the main steps of the design flow for DNA arrays (see Figure 1, solid arcs), noting the similarity to the VLSI design flow and briefly reviewing previous work. Then we discuss how the current DNA array design flow may be enhanced by adding *flow-awareness* to each optimization step and introducing *feedback loops* between steps - techniques that have proved very effective in the VLSI design context [11, 30].

2.1 Probe Selection

Analogous to logic synthesis in VLSI design, the probe selection step is responsible for implementing the desired functionality of the DNA array. Although probe selection is application-dependent, several underlying selection criteria are common to all designs, regardless of the intended application [1, 2, 26, 4, 21, 29].

First, in order to meet array functionality, the selected probes must have low hybridization energy for their intended targets and high hybridization energy for all other target sequences. Hence, a standard way of selecting probes is to select a probe of minimum hybridization energy from the set of probes which maximize the minimum number of mismatches with all other sequences [26]. Second, since selected probes must hybridize under similar operating conditions, they must have similar melting temperatures.[1] Finally, to simplify array design, probes are often constrained to be substrings of a predetermined nucleotide deposition sequence. Typically, there are multiple probe candidates satisfying these constraints.

2.2 Deposition Sequence Design

The number of synthesis steps directly affects manufacturing time and the number of masks in the mask set, and also directly affects the quantity of defective probes synthesized on the chip. Therefore, a basic optimization in DNA array design is to minimize the number of synthesis steps. In the simplest model, this optimization has been reformulated as the classical *shortest common supersequence* (SCS) problem [24, 34]: Given a finite alphabet Σ (for DNA arrays $\Sigma = \{A, C, T, G\}$) and a set $P = \{p_1, ..., p_t\} \subseteq \Sigma^n$ of probes, find a minimum-length string $s_{opt} \in \Sigma^*$ such that every string of P is a subsequence of s_{opt}. (A string p_i is a subsequence of s_{opt} if s_{opt} can be obtained from p_i by inserting zero or more symbols from Σ.) The SCS problem has been studied for over two decades from the point of view of computational complexity, probabilistic and worst-case analysis, approximation algorithms and heuristics, experimental studies, etc. (see, e.g., [5, 6, 7, 9, 14, 15, 20]).

The general SCS problem is NP-hard, and cannot be approximated within a constant factor in polynomial time unless $P = NP$ [20]. On the other hand, a $|\Sigma|$-approximation is produced by using the *trivial periodic supersequence* $s = (x_1 x_2 \ldots x_{|\Sigma|})^n$, where $\Sigma = \{x_1, x_2, \ldots, x_{|\Sigma|}\}$ Better results are produced in practice by a simple greedy algorithm usually referred to as the "majority merge" algorithm [14], or variations of it that add randomization, lookahead, bidirectionality, etc. (see, e.g., [24]).

Current DNA array design methodologies bypass the deposition design step and use a predefined, typically periodic deposition sequence such as $ACTGACTG\ldots$ (see, e.g., [24, 34]).

2.3 Design of Control and Test Structures

DNA array manufacturing defects can be classified as *non-catastrophic*, i.e., defects that affect the reliability of hybridization results, but do not compromise its functionality when maintained within reasonable limits, and *catastrophic*, i.e., defects that render the chip unusable. Non-catastrophic defects are caused by systematic error sources in the VLSIPS manufacturing process, such as unintended illumination due to diffraction, internal reflection, and scattering. Their impact on hybridization reliability of the chip is reduced by using the Perfect Match/Mismatch strategy [1, 27], which is also used to reduce the contribution of

[1] Below the melting temperature, two complementary strands of DNA are always bound to each other, while above it they separate. A practical method for estimating the melting temperature is suggested in [21].

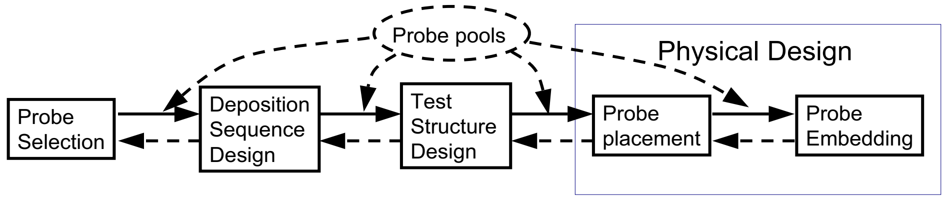

Figure 1. A typical DNA array design flow with solid arcs and proposed enhancements represented by dashed arcs.

background and cross-hybridization [27]. Under this strategy, a single nucleotide polymorphic probe ("Mismatch Probe") is synthesized next to each functional probe ("Perfect Match Probe"). Catastrophic defects are caused by missing, out-of-order, or incomplete synthesis steps, wrong or misaligned masks, etc.

DNA array test structures are the equivalent of built-in self-test (BIST) structures in VLSI design, and seeking to detect catastrophic manufacturing defects. The current approach to detecting catastrophic defects in DNA arrays is to synthesize a small set of test probes. Hubbell and Pevzner [19] have recently introduced a combinatorial approach that constructs such a small set of *fidelity* probes that, besides detecting manufacturing defects, can be used to identify the erroneous manufacturing steps. The approach relies on using multiple identical copies of the same fidelity probe, deliberately manufactured using different synthesis steps. A known target is then hybridized to these probes, and hybridization results reflect the quality of the manufacturing process. Further recent progress on the test structure design problem include results of [3, 8, 31].

2.4 Physical Design

Physical design for DNA arrays is equivalent to the physical design phase in VLSI design. It consists of two steps: *probe placement*, which is responsible for mapping selected probes onto locations on the chip, and probe embedding, which embeds each probe into the deposition sequence (i.e., determines synthesis steps for all nucleotides in the probe). The result of probe placement and embedding is the complete description of the reticles used to manufacture the array.

Under ideal manufacturing conditions, the functionality of a DNA array is not affected by the placement of the probes on the chip or by the probe synthesis schedules. In practice, since manufacturing process is prone to errors, probe locations and synthesis schedules affect to a great degree the hybridization sensitivity and ultimately the functionality of the DNA array. There are several types of synthesis errors that take place during array manufacturing. First, a probe may not loose its protective group when exposed to light, or the protective group may be lost but the nucleotide to be synthesized may not attach to the probe. Second, due to diffraction, internal reflection, and scattering, unintended illumination may occur at sites that are geometrically close to intentionally exposed regions. The first type of manufacturing errors can be effectively controlled by careful choice of manufacturing process parameters, e.g., by proper control of exposure times and by insertion of correction steps that irrevocably end synthesis of all probes that are unprotected at the end of a synthesis step [1]. Errors of the second type result in synthesis of unforeseen sequences in masked sites and can compromise interpretation of hybridization intensities. To reduce such uncertainty, one can exploit the freedom available in assigning probes to array sites during placement and in choosing among multiple probe embeddings, when available. The objective of probe placement and embedding algorithms is therefore to minimize the sum of border lengths in all masks, which directly corresponds to the magnitude of the unintended illumination effects. Reducing these effects improves the signal to noise ratio in image analysis after hybridization, and thus permits smaller array sites or more probes per array [18].

The border minimization problem was first considered for *uniform arrays* (i.e., arrays containing all possible probes of a given length) by Feldman and Pevzner [12], who proposed an optimal solution based on 2-dimensional Gray codes. Hannenhalli et al. [17] gave a heuristic for synthesizing arbitrary sets of probes, but considered only *synchronous* probe embeddings. This embedding method requires a periodic deposition sequence, and mandates that the i^{th} nucleotide of a probe be embedded at the unique matching position available in the i^{th} period (see Figure 2(b)). The method in [17] is to order the probes in a traveling salesman problem (TSP) tour that heuristically minimizes the total Hamming distance between neighboring probes. The tour is then *threaded* into the two-dimensional array of sites, using a technique similar to one previously used in VLSI design [25]. For the same synchronous context, [22] suggested an *epitaxial*, or "seeded crystal growth", placement heuristic similar to heuristics explored in the VLSI circuit placement literature by [28, 32].

The general border minimization problem, which allows arbitrary, or *asynchronous* probe embeddings (see Figure 2(c)), was introduced by Kahng et al. [22]. They proposed a dynamic programming algorithm that embeds a given probe optimally with respect to fixed embeddings of the probe's neighbors. This algorithm is used as a building block for designing several algorithms that improve a placement by re-embedding probes, but without re-placing them. Very recently, [23] proposed methods with near-linear run-

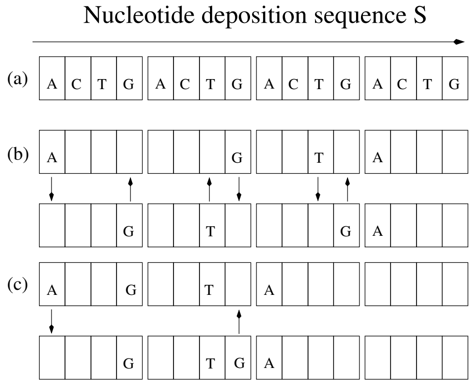

Figure 2. (a) Periodic deposition sequence. (b) Synchronous embedding of the probes $AGTA$ and $GTGA$ gives 6 border conflicts (indicated by arrows). (c) "As soon as possible" asynchronous embedding of the probes $AGTA$ and $GTGA$ gives only 2 border conflicts.

time combining simple ordering-based heuristics for *initial placement*, such as lexicographic sorting followed by threading, with heuristics for *placement improvement*, such optimal reassignment of an "independent" set of probes [33] chosen from a sliding window [10], or a row-based implementation of the epitaxial algorithm that speeds-up the computation by considering only a limited number of candidates when filling each array site.[2]

2.5 Flow Enhancements

The current design flow can be significantly improved by introducing flow-aware problem formulations, adding feedback loops between optimization steps, and/or integrating multiple optimizations. These enhancements, which are represented schematically in Figure 1 by the dashed arcs, are similar to flow enhancements that have proved very effective in the VLSI design context [11, 30].

In this paper we concentrated on two such enhancements, both aiming for further reductions in total border length. The first enhancement is a tighter integration between probe placement and embedding; this enhancement is discussed in Section 4. The second enhancement is the integration between physical design and probe selection, which is achieved by passing the entire pools of candidates available for each probe to the physical design step. As shown in Section 5, this enhancement enables significant improvements (up to 15%) in border length compared to best previous flows [23].

Other feedback loops and integrated optimizations are possible but are not explored in this paper. Faster and more targeted probe selection may be achievable by adding a feedback loop to provide updated selection rules and parameters to the probe selection step. Integrating deposition sequence design with probe selection may lead to further reductions in the number of masks by exploiting the freedom available in choosing the candidates for each probe. Although we show in Section 6 that a simple method for integrating physical design with deposition sequence design leads to insignificant improvements in solution quality, this does not rule out future improvements from tighter integrations between the two steps, such as the addition of a feedback loop transferring to the deposition sequence design step conflict map information (i.e., border length distribution across deposition steps) generated by physical design.

3 Formulation and Core Algorithms for Integrated Probe Selection and DNA Array Physical Design

In this section we formally introduce the border-length minimization objective. We then give an integrated formulation capturing several of the flow enhancements suggested in the previous section and further studied in Sections 4-5. We conclude the section by describing two algorithms used as building blocks in these studies.

Let $M_1, M_2, \ldots, M_K$ denote the sequence of masks used in the synthesis of an array, and let $s_i \in \{A, C, T, G\}$ be the nucleotide synthesized after exposing mask M_i. Every array probe must be a subsequence of the *nucleotide deposition sequence* $S = s_1 s_2 \ldots s_K$. Often, a probe corresponds to multiple subsequences of S, and one such subsequence must be chosen as the synthesis schedule for the probe. Clearly, the geometry of the masks is uniquely determined by the placement of the probes on the array and the particular synthesis schedule used for each probe.

Formally, array design can be viewed as a *3-dimensional placement* problem [22]: two dimensions represent the site array, and the third dimension represents the nucleotide deposition sequence S (see Figure 3). Each layer in the third dimension corresponds to a mask that induces deposition of a particular nucleotide (A, C, G, or T); a probe is *embedded* within a "column" of this 3-dimensional placement representation. Border length of a given mask is computed as the number of *conflicts*, i.e., pairs of adjacent exposed and masked sites in the mask. Given two adjacent embedded probes p and p', the *conflict distance* $d(p, p')$ is the number of conflicts between the corresponding columns. The border length of the embedding is the sum of conflict distances between adjacent probes, and the border length minimization problem seeks to minimize this quantity.

To integrate probe selection and physical design, we pass the entire pools of candidates for each probe to the physical design step (Figure 1). This gives additional freedom during placement and embedding, and may potentially reduce final border cost. Indeed, theoretical analysis omitted from

[2]The work of [23] also extends probe placement algorithms to handle practical concerns such as pre-placed control probes, presence of polymorphic probes, unintended illumination between non-adjacent array sites, and position-dependent border conflict weights.